

AMENDMENTS TO THE CLAIMS

This listing of claims will replace all prior versions and listings of claims in the application:

LISTING OF CLAIMS:

1.-33. (canceled).

34. (currently amended): A photosensitive composition remover used for removal of an uncured photosensitive composition, which remover consists essentially of 10 to 20 percent by mass of one or more aromatic hydrocarbon(s) having 9 carbon atoms or more within the molecule and 80 to 90 percent by mass of one or more other solvent(s) other than aprotic polar solvents,

wherein the aromatic hydrocarbon is basically C₉ or C₁₀-based,

wherein the photosensitive composition remover is used for removal of a photosensitive composition containing a pigment;

wherein the other solvent other than aprotic polar solvents is two or more of propylene glycol monomethyl ether, propylene glycol monomethyl ether acetate, butyl acetate, ethyl 3-ethoxypropionate, methyl 3-methoxypropionate, and cyclohexanone;

wherein 30 to 60 percent by mass of propylene glycol monomethyl ether is present in the remover;

wherein the aromatic hydrocarbon which is basically C₉ or C₁₀-based comprises a solvent naphtha.

35. (new): A photosensitive composition remover used for removal of an uncured photosensitive composition, which remover consists essentially of 10 to 20 percent by mass of

one or more aromatic hydrocarbon(s) having 9 carbon atoms or more within the molecule and 80 to 90 percent by mass of one or more other solvent(s) other than aprotic polar solvents,

wherein the aromatic hydrocarbon is basically C₉ or C₁₀-based,

wherein the photosensitive composition remover is used for removal of a photosensitive composition containing a pigment;

wherein the other solvent other than aprotic polar solvents is at least one selected from the group consisting of glycol ethers excluding dipropylene glycol monomethyl ether, glycol ether carboxylates, carboxylic acid esters excluding ethyl acetate and amyl acetate, hydroxycarboxylic acid esters, ketones, alkoxycarboxylic acids esters, and cyclic ethers; and

wherein the aromatic hydrocarbon which is basically C₉ or C₁₀-based comprises at least one selected from the group consisting of a basically C₉ alkylbenzene-based mixed solvent, a basically C₁₀ alkylbenzene-based mixed solvent, and a basically C₁₀ alkylbenzene-alkylnaphthalene-based mixed solvent.

36. (new): A photosensitive composition remover as set forth in claim 35, wherein 30 to 60 percent by mass of propylene glycol monomethyl ether is present in the remover.

37. (new): A photosensitive composition remover as set forth in claim 35, used for removal of an acrylic photosensitive composition containing a pigment.

38. (new): A photosensitive composition remover as set forth in claim 35, wherein the remover consists of solvents.

39. (new): A photosensitive composition remover as set forth in claim 35, wherein the other solvent other than aprotic polar solvents is two or more of propylene glycol monomethyl ether, propylene glycol monomethyl ether acetate, butyl acetate, ethyl 3-ethoxypropionate, methyl 3-methoxypropionate, and cyclohexanone.

40. (new): A photosensitive composition remover as set forth in claim 36, wherein the other solvent other than aprotic polar solvents other than propylene glycol monomethyl ether is at least one selected from the group consisting of propylene glycol monomethyl ether acetate, butyl acetate, cyclohexanone, methyl 3-methoxypropionate and ethyl 3-ethoxypropionate.

41. (new): A photosensitive composition remover used for removal of an uncured photosensitive composition, which remover consists essentially of 10 to 20 percent by mass of one or more aromatic hydrocarbon(s) having 9 carbon atoms or more within the molecule and 80 to 90 percent by mass of one or more other solvent(s) other than aprotic polar solvents,

wherein the aromatic hydrocarbon is basically C₉ or C₁₀-based,

wherein the photosensitive composition remover is used for removal of a photosensitive composition containing a pigment;

wherein the other solvent other than aprotic polar solvents comprises a glycol monoalkyl ether and at least one selected from the group consisting of glycol ether carboxylates, carboxylic acid esters, hydroxycarboxylic acid esters, ketones, alkoxycarboxylic acids esters, and cyclic ethers; and

wherein the aromatic hydrocarbon which is basically C₉ or C₁₀-based comprises at least one selected from the group consisting of a basically C₉ alkylbenzene-based mixed solvent, a basically C₁₀ alkylbenzene-based mixed solvent, and a basically C₁₀ alkylbenzene-alkylnaphthalene-based mixed solvent.

42. (new): A photosensitive composition remover used for removal of an uncured photosensitive composition, which remover comprises 1 to 80 percent by mass of at least one type of aromatic hydrocarbon having 9 carbon atoms or more within the molecule, wherein the at least one type of aromatic hydrocarbon having 9 carbon atoms or more within the molecule

comprises at least one selected from the group consisting of a basically C₉ alkylbenzene-based mixed solvent, a basically C₁₀ alkylbenzene-based mixed solvent, and a basically C₁₀ alkylbenzene-alkylnaphthalene-based mixed solvent.

43. (new): A photosensitive composition remover as set forth in claim 42, wherein the aromatic hydrocarbon having 9 carbon atoms or more within the molecule is an alkylbenzene having a boiling point of 150 to 250°C.

44. (new): A photosensitive composition remover as set forth in claim 42, having a composition selected from the group consisting of

a composition of 20 to 80 percent by mass of one or more aromatic hydrocarbon(s) having 9 carbon atoms or more within the molecule and 20 to 80 percent by mass of one or more aprotic polar solvent(s) when the remover consists essentially of one or more aromatic hydrocarbon(s) having 9 carbon atoms or more within the molecule and one or more aprotic polar solvent(s);

a composition of 10 to 20 percent by mass of one or more aromatic hydrocarbon(s) having 9 carbon atoms or more within the molecule and 80 to 90 percent by mass of one or more other solvent(s) other than aprotic polar solvents when the remover consists essentially of one or more aromatic hydrocarbon(s) having 9 carbon atoms or more within the molecule and one or more other solvent(s) other than aprotic polar solvents; and

a composition of 20 to 30 percent by mass of one or more aromatic hydrocarbon(s) having 9 carbon atoms or more within the molecule, 1 to 20 percent by mass of one or more aprotic polar solvent(s), and 55 to 70 percent by mass of one or more other solvent(s) other than aprotic polar solvents when the remover comprises one or more aromatic hydrocarbon(s) having

9 carbon atoms or more within the molecule, one or more aprotic polar solvent(s), and one or more other solvent(s) other than aprotic polar solvents.

45. (new): A photosensitive composition remover as set forth in claim 42, having a composition selected from the group consisting of

a composition of 20 to 40 percent by mass of one or more aromatic hydrocarbon(s) having 9 carbon atoms or more within the molecule and 60 to 80 percent by mass of one or more aprotic polar solvent(s) when the remover consists essentially of one or more aromatic hydrocarbon(s) having 9 carbon atoms or more within the molecule and one or more aprotic polar solvent(s);

a composition of 10 to 20 percent by mass of one or more aromatic hydrocarbon(s) having 9 carbon atoms or more within the molecule and 80 to 90 percent by mass of one or more other solvent(s) other than aprotic polar solvents, wherein the remover comprises 30 to 60 percent by mass of propylene glycol monomethyl ether, when the remover consists essentially of one or more aromatic hydrocarbon(s) having 9 carbon atoms or more within the molecule and one or more other solvent(s) other than aprotic polar solvents; and

a composition of 20 to 30 percent by mass of one or more aromatic hydrocarbon(s) having 9 carbon atoms or more within the molecule, 3 to 20 percent by mass of one or more aprotic polar solvent(s), and 55 to 70 percent by mass of one or more other solvent(s) other than aprotic polar solvents, the aprotic polar solvent(s) being at least one selected from the group consisting of N,N-dimethylformamide and N,N-dimethylacetamide, and the other solvent(s) other than aprotic polar solvents being at least one selected from the group consisting of propylene glycol monomethyl ether acetate, cyclohexanone, methyl 3-methoxypropionate and ethyl 3-ethoxypropionate, when the remover comprises one or more aromatic hydrocarbon(s)

having 9 carbon atoms or more within the molecule, one or more aprotic polar solvent(s), and one or more other solvent(s) other than aprotic polar solvents.

46. (new): A photosensitive composition remover as set forth in claim 42, comprising 20 to 40 percent by mass of one or more aromatic hydrocarbon(s) having 9 carbon atoms or more within the molecule and 60 to 80 percent by mass of one or more aprotic polar solvent(s).

47. (new): A photosensitive composition remover as set forth in claim 42, comprising 10 to 20 percent by mass of one or more aromatic hydrocarbon(s) having 9 carbon atoms or more within the molecule and 80 to 90 percent by mass of one or more other solvent(s) other than aprotic polar solvents, wherein the remover comprises 30 to 60 percent by mass of propylene glycol monomethyl ether.

48. (new): A photosensitive composition remover as set forth in claim 42, comprising 20 to 30 percent by mass of one or more aromatic hydrocarbon(s) having 9 carbon atoms or more within the molecule, 3 to 20 percent by mass of one or more aprotic polar solvent(s), and 55 to 70 percent by mass of one or more other solvent(s) other than aprotic polar solvents, wherein the aprotic polar solvent is at least, one selected from the group consisting of N,N-dimethylformamide and N,N-dimethylacetamide, and the other solvent other than aprotic polar solvents is at least one selected from the group consisting of propylene glycol monomethyl ether acetate, cyclohexanone, methyl 3-methoxypropionate and ethyl 3-ethoxypropionate.

49. (new): A photosensitive composition remover as set forth in claim 44, wherein the aprotic polar solvent is at least one selected from the group consisting of chain amide compounds, cyclic amide compounds, sulfur compounds, and cyclic esters.

50. (new): A photosensitive composition remover as set forth in claim 44, wherein the aprotic polar solvent is at least one selected from the group consisting of formamide, N-methylformamide, N,N-dimethylformamide, N-ethylformamide, N,N-diethylformamide, N,N-dimethylacetamide, tetramethyl urea, N-methyl-2-pyrrolidone, N-methylimidazolidinone, dimethyl sulfoxide, sulfolane, and γ -butyrolactone.

51. (new): A photosensitive composition remover as set forth in claim 47, wherein the other solvent other than aprotic polar solvents is at least one selected from the group consisting of glycol ethers, glycol ether carboxylates, carboxylic acid esters, hydroxycarboxylic acid esters, ketones, alcohols, alkoxycarboxylic acids esters, and cyclic ethers.

52. (new): A photosensitive composition remover as set forth in claim 42, used for removal of a photosensitive composition containing a pigment.

53. (new): A photosensitive composition remover as set forth in claim 42, used for removal of an acrylic-type photosensitive composition containing a pigment.